

ABSTRACT

A liquid chemical processing device that reduces variation in resist removal for each substrate includes: a processing tank (10a) in which resist removal processing is performed by immersing substrates (4) in a chemical (6); a plurality of holders (22) configured to hold the substrates (4) in a vertical posture; vertical drivers (20) configured to individually and vertically drive the holders (22); and a chuck (55) configured to disengageably chuck the substrates (4), wherein the vertical drivers (20) are configured to individually and vertically move the holders (22) between an immersed position where the substrates (4) are immersed in the chemical (6) and a non-immersed position where the substrates (4) are lifted up from the chemical (6), and the substrates (4) held by the holders (22) are subjected to the resist removal processing in a single wafer manner.